

ABSTRACT OF THE DISCLOSURE

A chemical vapor deposition process for laying down a tin or titanium oxide coating on a glass substrate through the use of an organic oxygen-containing compound and the corresponding metal tetrachloride. The organic oxygen compound is preferably an ester having an alkyl group with a β hydrogen in order to obtain a high deposition rate. The resulting article has a tin or titanium oxide coating which can be of substantial thickness because of the high deposition rates attainable with the novel process, and, in the case of titanium oxide coating possesses a desirable refractive index greater than 2.4. The coating growth rates resulting from the method of the present invention may be at least 130Å per second.

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